



SFP-100D Polishing Process

Convex PC Polishing Using Non Pre-Radiused 2.5mm Zirconia Ferrules

Polishing Step	Polishing Pad	Polishing Film	Polishing Fluid	Polishing Time
Epoxy Removal	PG10-490	GA10 (1)	None	0.5
Course Polishing	PG10-490	GA10 (2)	None	0.5
Convex Forming	PR10-500	GA10	Distilled Water	0.5
Rough Polishing	PR10-500	DR4D-9U (3)	Distilled Water	2.0
Middle Polishing	PR10-500	DM4D-3U (3)	Distilled Water	0.5
Final Polishing	PR10-500 & SP10-005	HF4D (4)	Distilled Water	1.0 - 2.0
Cleaning	PR10-500	CF4D	Distilled Water	0.2

Convex PC Polishing Using Pre-Radiused 2.5mm Zirconia Ferrules

Polishing Step	Polishing Pad	Polishing Film	Polishing Fluid	Polishing Time
Epoxy Removal	PR10-500	GA10 (1)	Distilled Water	0.5
Rough Polishing	PR10-500	DR4D-9U (3)	Distilled Water	0.5
Middle Polishing	PR10-500	DM4D-3U (3)	Distilled Water	0.5
Final Polishing	PR10-500 & SP10-005	HF4D (4)	Distilled Water	1.0 - 2.0
Cleaning	PR10-500	CF4D	Distilled Water	0.2

NOTES:

- (1) For this step only, do not clamp the holder for the first 20 rotations of the turntable. This will prevent chipping and cracking.
- (2) After epoxy removal, clean the GA10 film with a lint-free tissue and Alcohol. Inspect the surface for visible damage. Replace the film only if necessary.
GA10 may be used up to 5 times ea. Sheet.
- (3) After each use, clean the DR4D and the DM4D-BL films with a lint-free tissue and alcohol. These films may be used up to 20 times ea.
- (4) HF4D may be used up to 5 times ea. Sheet. As it is a very fine grain, please make sure the sticky side is up when polishing.
- (5) CF4D will remove any remaining Silica particles after HF4D polishing.